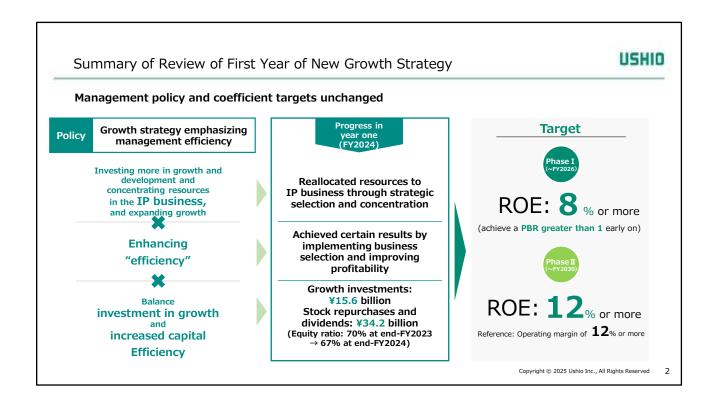
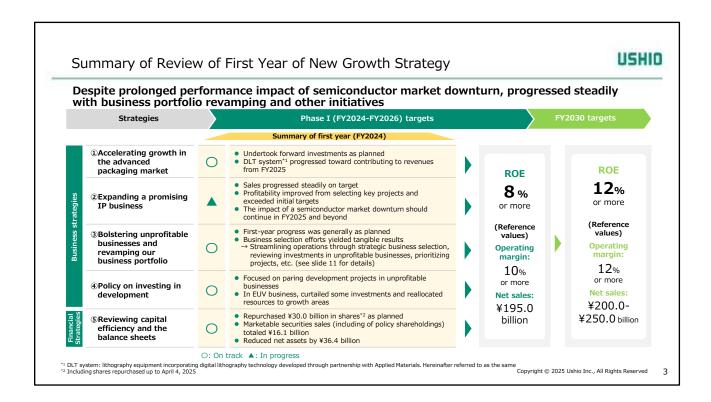


It has been one year since we announced our New Growth Strategy, and I will explain the progress made and the direction toward achieving our future goals.

Please note that the outlook, including FY2026, is based on information currently available. Changes in recent trends, such as the impact of U.S. tariff measures, are mostly not factored into forecasts due to difficulty in estimating their impact, except for some confirmed cases.

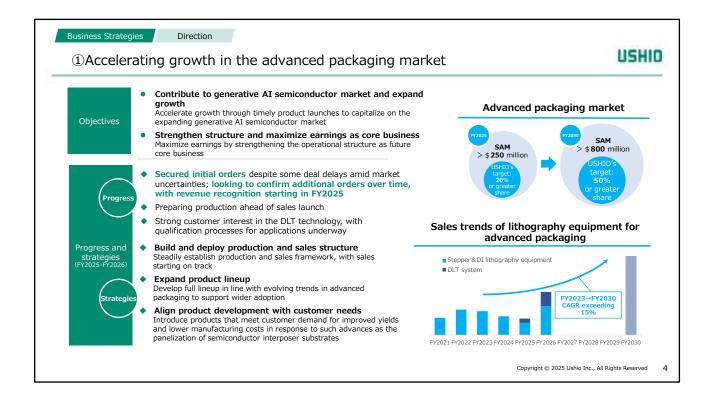


One year ago, we launched our new growth strategy with three major policies. We have been steadily advancing initiatives under each policy, and there are no changes to the coefficient targets and policies for Phase I in FY2026 and Phase II in FY2030 at this time.



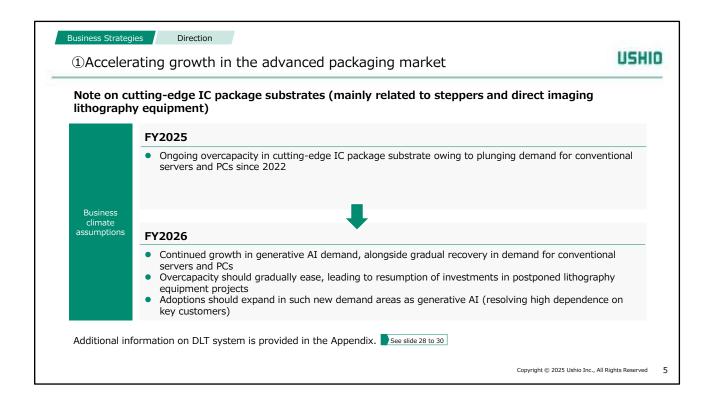
The initiatives under the "Business Strategy" and "Financial Strategy" have generally progressed as planned. However, Industrial Processes business continues to be affected by the prolonged semiconductor market downturn, and this impact is expected to persist beyond FY2025, requiring ongoing attention.

From the next page, I will explain the specific progress of each initiative and the future direction.



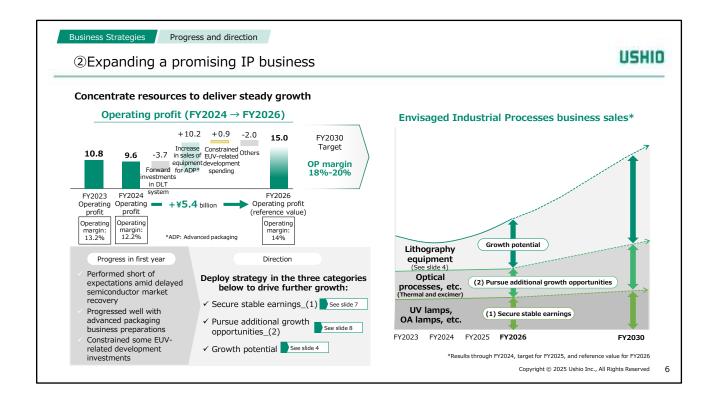
Regarding "accelerating growth in the advanced packaging market," some delays have occurred in certain deals of DLT system, the new lithography equipment, due to the current uncertain market environment. However, we have already secured initial orders, and revenue recognition will start in the second half of FY2025.

Evaluations by many customers are ongoing, and qualifications for adoption are expected to proceed sequentially.



In FY2026, we expect the overcapacity in the cutting-edge IC package substrate market, which is currently experiencing weak demand, to gradually be resolved. Along with the expansion of DLT system sales, sales of existing lithography equipment such as steppers and direct imaging lithography equipment are also expected to increase.

I will provide additional explanations about DLT system later.

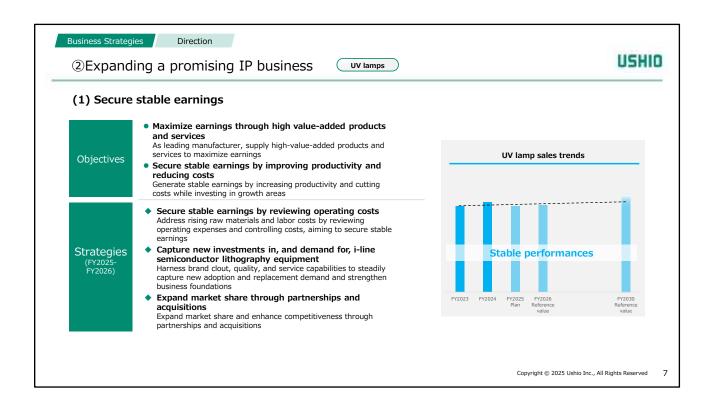


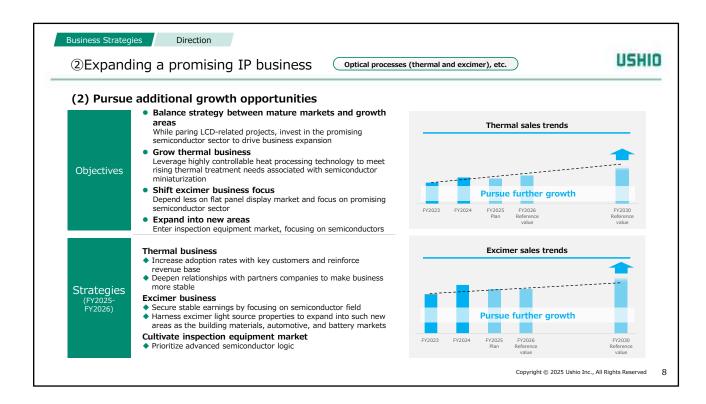
Regarding "expanding a promising Industrial Processes (IP) business," we plan to drive growth focusing on the advanced packaging business I just explained.

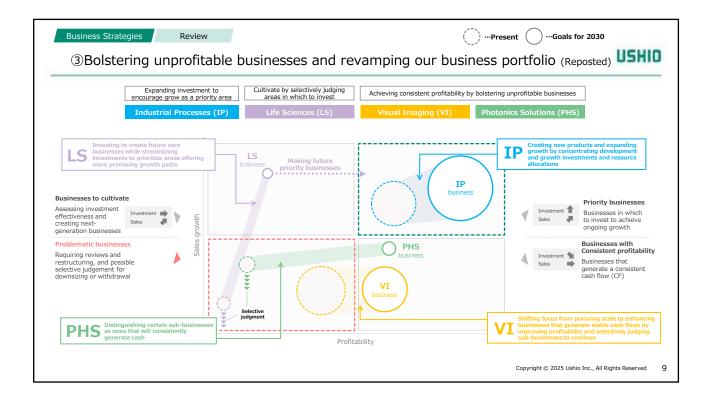
In addition to the significantly growing lithography equipment, we will pursue further growth potential in semiconductor-related products such as optical processes. By continuing to secure stable earnings mainly from UV lamps, we aim to steadily grow Industrial Processes business.

The direction and strategy for optical processes and exposure lamps are shown on slides 7 and 8, which you can review later.

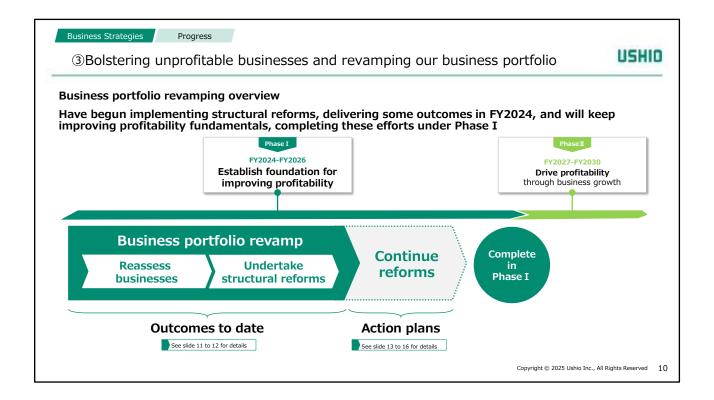
(Move on to slide 9)





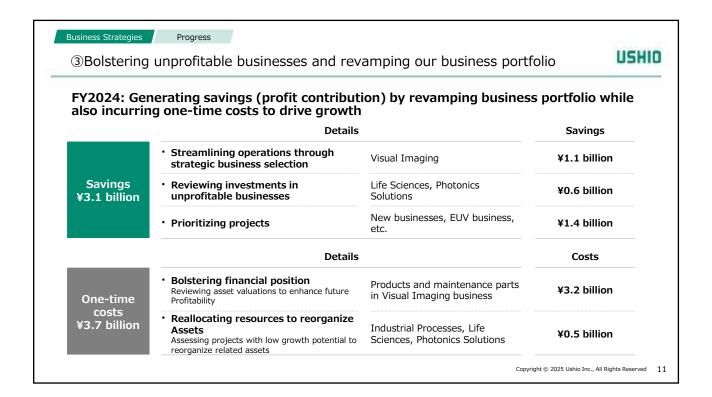


Regarding "bolstering unprofitable businesses and revamping our business portfolio," we are advancing initiatives in line with the directions previously outlined for each segment.

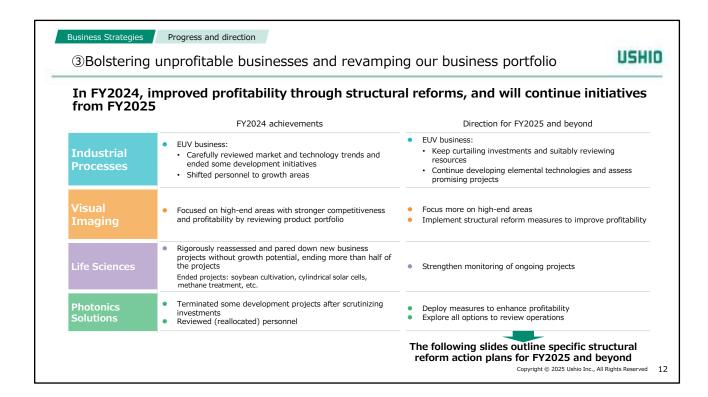


Regarding the progress of "revamping our business portfolio," we achieved certain results in the first year.

We will continue these efforts from FY2025 onward, aiming to complete the revamp by FY2026, the final year of Phase I.

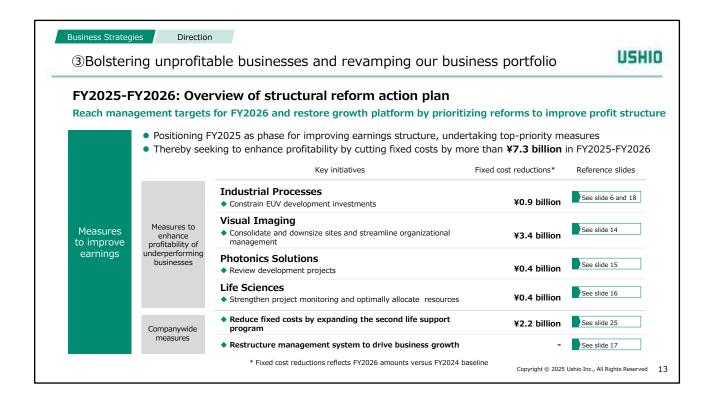


Through strategic business selection in each segment, we achieved a profit improvement of 3.1 billion yen in the first year. However, some one-time costs were also incurred.



The "strategic business selection" in each segment mainly involved rigorous evaluation and narrowing down of development projects. These efforts will continue beyond FY2025.

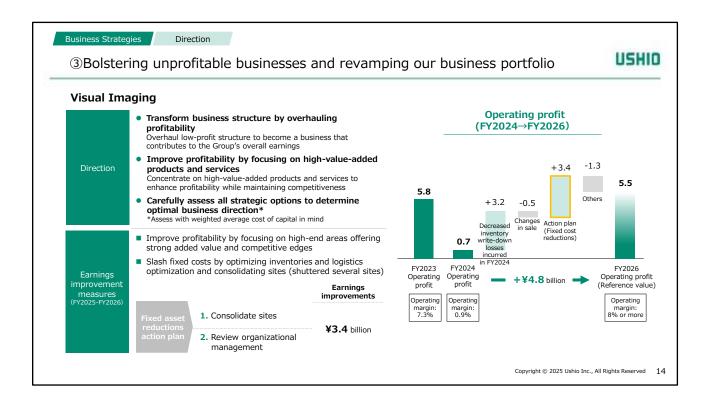
Specific action plans for FY2025 and beyond will be explained on the following pages.



This page summarizes the specific "structural reform action plan" aimed at improving the profit structure over the two years until FY2026, the final year of Phase I.

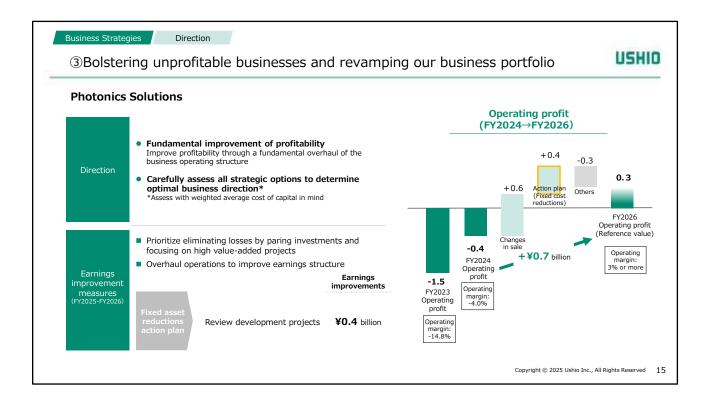
As stated, by advancing initiatives in each segment, we aim to reduce fixed costs by more than 7.3 billion yen in total.

Details are provided in the referenced slides, but I will explain only the key initiatives in major segments.



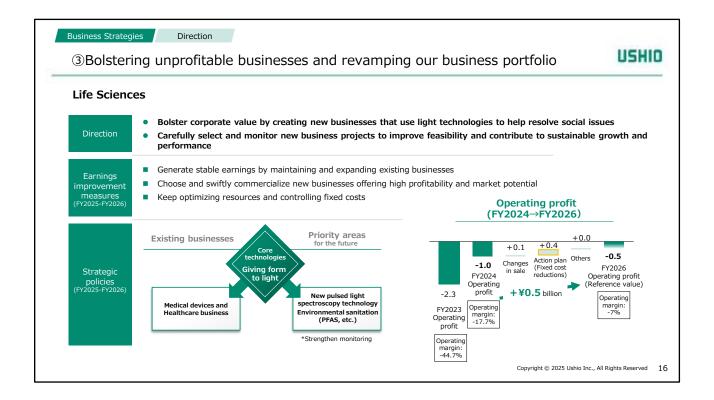
In Visual Imaging business, we aim to achieve a fundamental improvement in the profit structure by reducing fixed costs by 3.4 billion yen through consolidation of multiple sites and reviewing organizational management.

At the same time, we will conduct rigorous business assessments to determine the optimal direction for the business and carefully consider all possibilities.



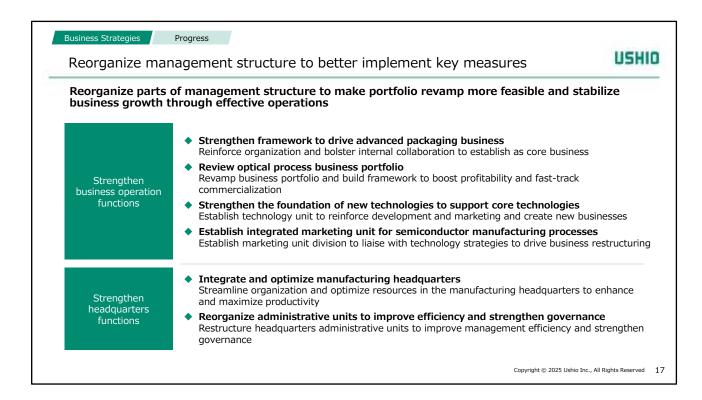
In Photonics Solutions business, we aim to move into the black by improving profitability through a fundamental overhaul of the business operating structure and restraining development projects.

Similarly to the Visual Imaging business, we will conduct strict business evaluations and continue to carefully consider all possible directions for the business.



In Life Sciences business, we will advance initiatives to create new businesses that contribute to enhancing corporate value in the future.

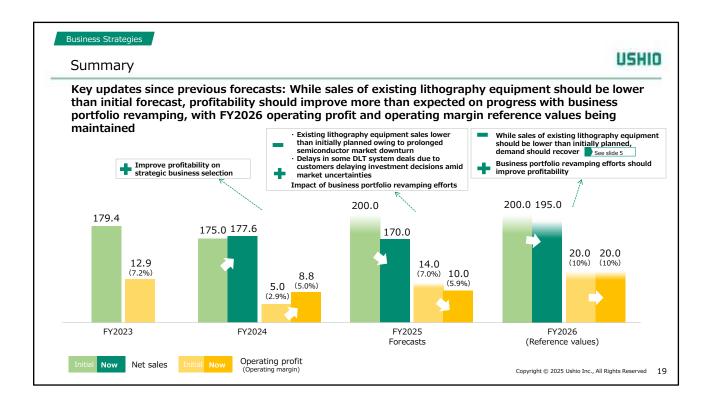
We will strengthen monitoring and conduct rigorous business assessments more than before to carefully select and focus on projects with higher feasibility.



To enhance the execution of the business strategies explained so far, we have made some revisions to the management structure. In particular, we strengthened the structure to steadily advance the advanced packaging business.

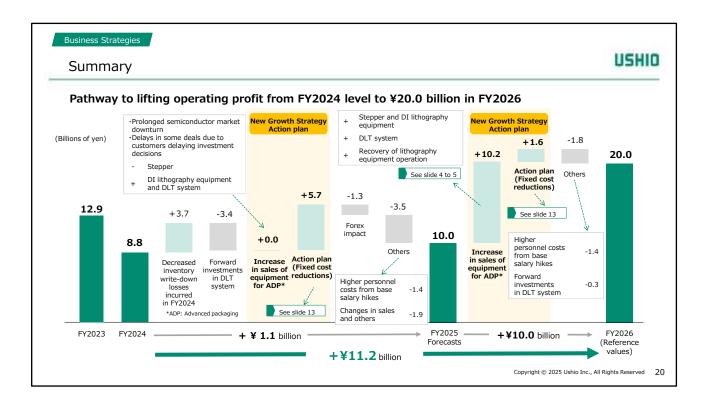
J. J, J	n invest	ing in de	evelopm	ent		USH
Undertake growth pot						n potential, curtailing investments without
	Cumulative					
	development Investment	Cumulative (FY2024-FY2026)				
(Billions of yen)	(FY2024- FY2026) After review		Now	Difference from previous time	Previous time	Review details and direction
			U	nderlined figure	es are revised	
IP Industrial Processes	22.0	Lithography equipment	Approx. 15.0	_	Approximately ¥15.0 billion	As planned, keep developing next-generation lithography equipment offering solid growth potential
		EUV	<u>Approx.</u> 3.0	-3.0	Approximately ¥6.0 billion	Investments curtailed. Development investments to be reducted from FY2025 onward Keep only developing elemental technologies and validating promising projects
		Others	<u>Approx.</u> 4.0	-3.0	Approximately ¥7.0 billion	Focus investments on such promising areas as optical proces (thermal and excimer) and semiconductor inspection light sources Constrain other projects with poor prospects
VI Visual Imaging	10.0	Imaging equipment	Approx. 10.0	-2.0	Approximately ¥12.0 billion	Pare development projects to focus on high-end models Note: Corrected previous figure (from ¥7.5 billion to ¥12.0 billion)
LS Life Sciences	6.0	_	Approx. 6.0	-2.5	Approximately ¥8.5 billion	Pare and constrain new business creation projects, and strengthen monitoring
PHS Photonics Solutions	2.5	_	Approx. 2.5	-1.0	Approximately ¥3.5 billion	Curb investments by reviewing and terminating some project
Total	40.5			-11.5	¥52.0 billion	

Regarding "policy on investing in development," by advancing strategic business selections, we narrowed down development projects and revised the cumulative development investment for the three years of Phase I to 11.5 billion yen.



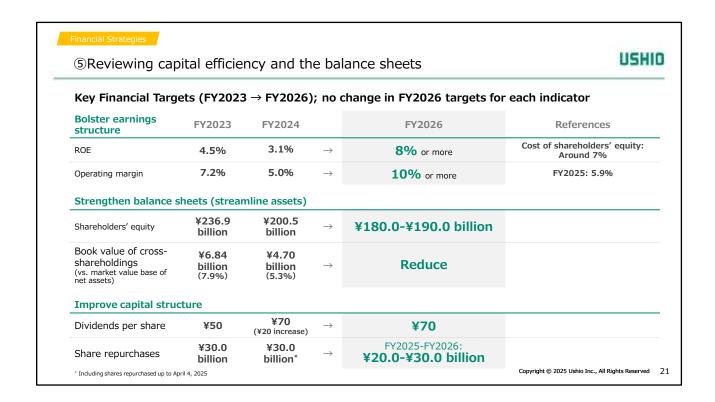
To summarize the business strategies explained so far, although there are impacts from the semiconductor market downturn and uncertainties in the market environment due to tariff trends, we plan to improve profitability by implementing structural reform measures in line with the business portfolio revamping policy.

While these are reference values, we are steadily progressing toward achieving the coefficient targets for FY2026.

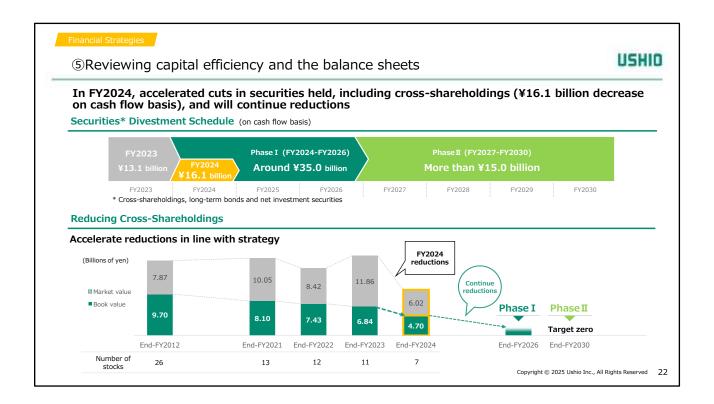


In FY2024, operating profit was 8.8 billion yen. To achieve the management target of ROE of 8% or more by FY2026, we will focus on expanding growth in the advanced packaging business and executing the structural reform action plan.

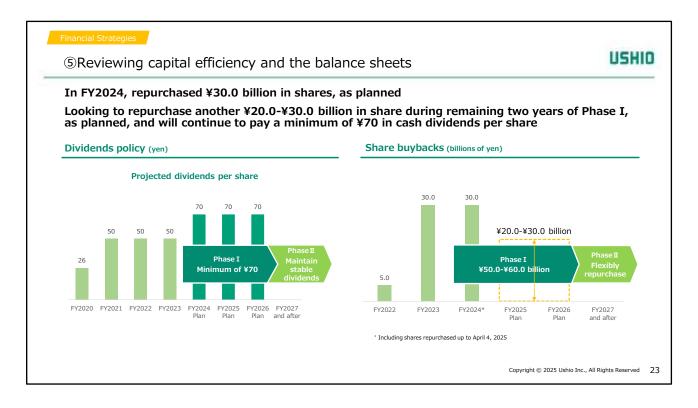
This concludes the explanation of the business strategy.



Next, regarding the financial strategy, the initiatives for FY2024 proceeded as planned. There are no changes to the direction we aim for in FY2026.



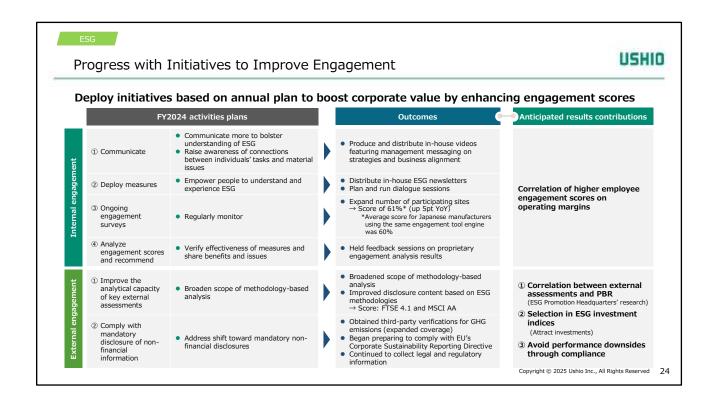
Regarding securities, including cross-shareholdings, we plan to reduce them by approximately 35 billion yen during Phase I. In the first year, FY2024, we sold 16.1 billion yen worth of securities. We will continue to proceed with the reduction.



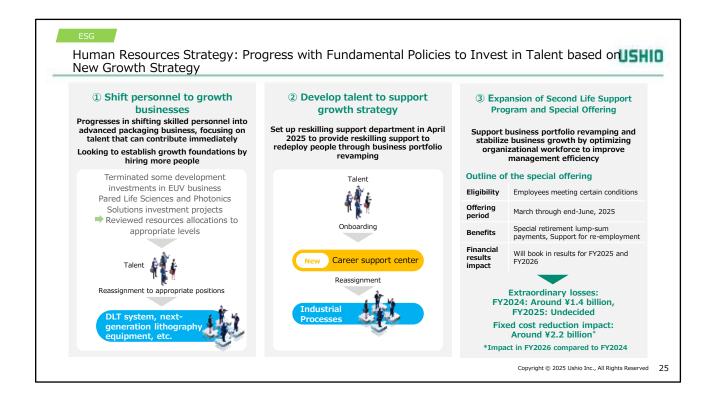
Shareholder returns were carried out as planned in FY2024. In FY2025, we will continue the minimum dividend of 70 yen per share in line with our policy.

For share buybacks, we plan to execute within the set framework as planned, targeting 20 to 30 billion yen over FY2025 and FY2026.

Details on other indicators are provided in the Appendix, which you can review later.

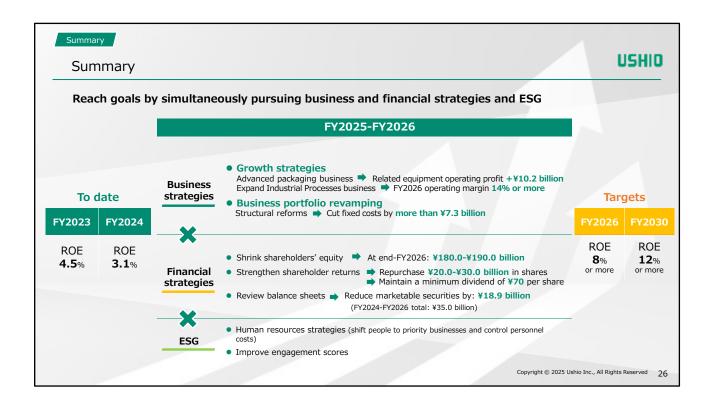


We are steadily advancing various ESG initiatives. These efforts aim to further enhance corporate value.



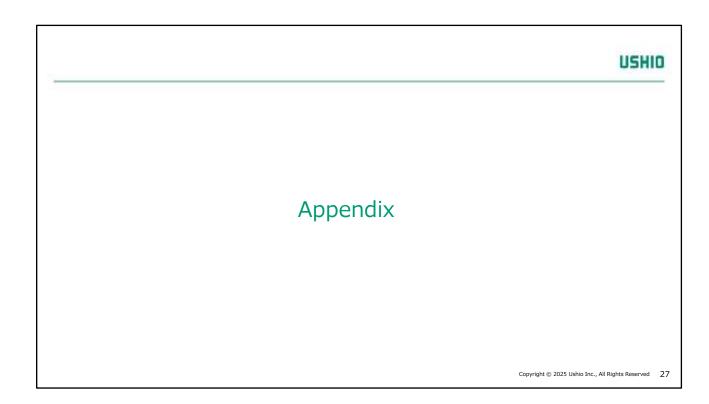
Under the policy of shifting personnel to growth businesses, we have advanced reskilling and talent development initiatives.

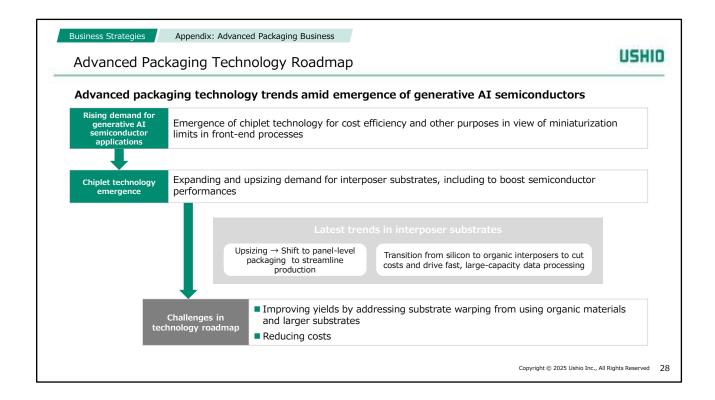
Additionally, we are improving management efficiency by expanding the Second Life Support Program.



To summarize, by simultaneously advancing the three strategies— "Business Strategy," which involves both growth strategy and structural reforms, "Financial Strategy," and "ESG"—we will steadily work toward achieving our targets of ROE of 8% or more in Phase I and 12% or more in Phase II.

(Move on to slide 28)



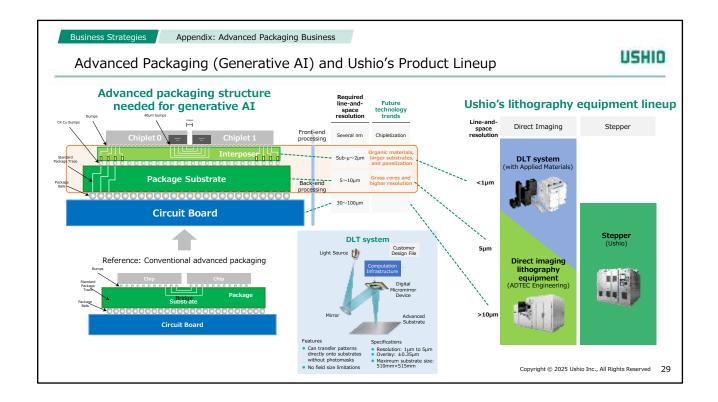


Finally, I would like to add some remarks about the advanced packaging business.

In the advanced packaging area, demand is expanding and technological trends are changing, presenting significant business opportunities.

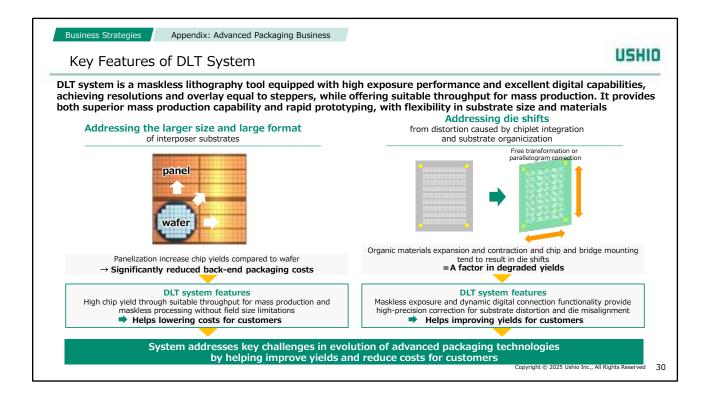
Driven by the rise of generative AI semiconductors, chiplet technology has emerged in next-generation semiconductor packaging. This is expected to drive further technological innovation, especially in interposer substrates.

At the same time, we recognize that there are many challenges in advancing these technology roadmaps, and we believe Ushio's lithography equipment can contribute to solving these challenges.



When organizing the lineup of next-generation semiconductor package substrates driven by the rise of generative AI semiconductors and Ushio's lithography equipment, it forms the image as described.

With the addition of DLT system through our partnership with Applied Materials, we are establishing a platform to reliably provide products that meet the evolution and growing demand of next-generation semiconductor package substrates.



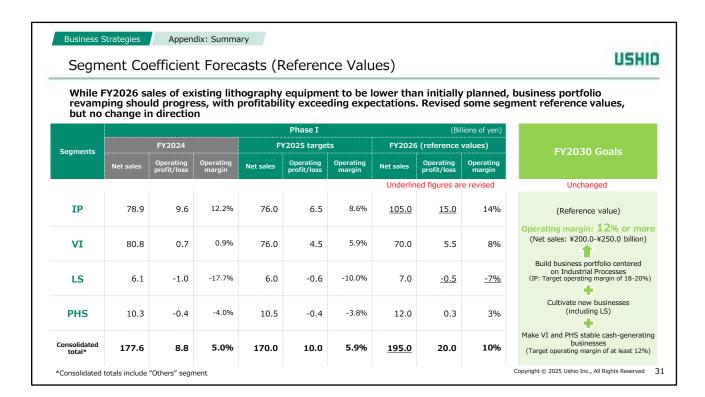
Let me once again explain the main features of DLT system.

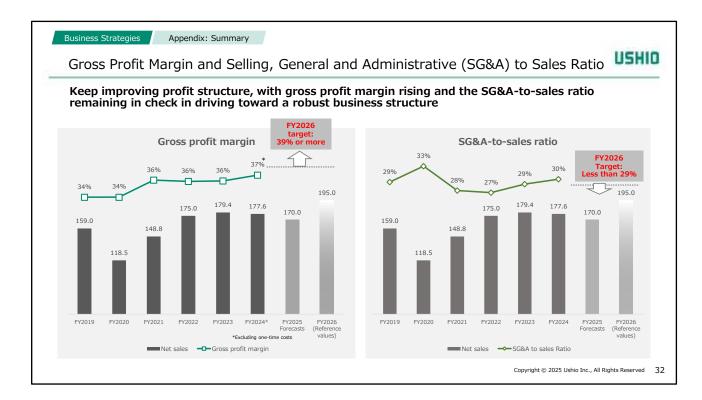
The DLT system is a maskless system equipped with high exposure performance and excellent digital functions. It achieves resolution and overlay equal to steppers, as well as throughput suitable for mass production.

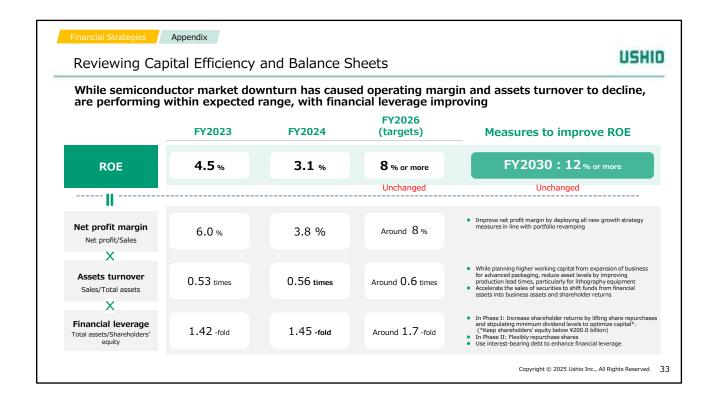
It also provides both superior mass production capability and rapid prototyping, with flexibility in substrate size and materials.

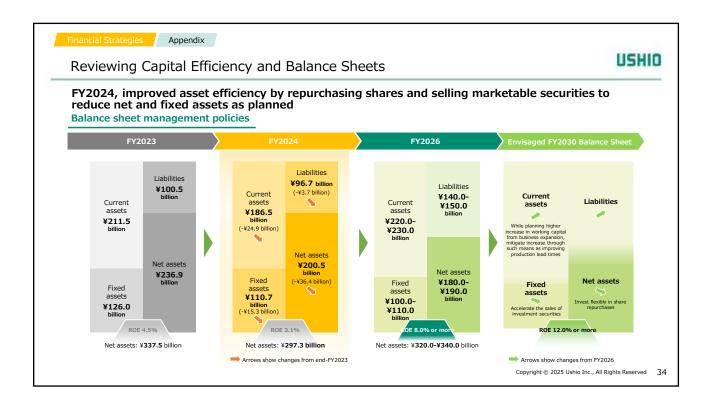
This system addresses challenges in advancing next-generation packaging technologies, such as addressing larger format and die shifts caused by chiplet integration. It contributes to improving yield and reducing costs for our customers.

Please look forward to it. This concludes my explanation.

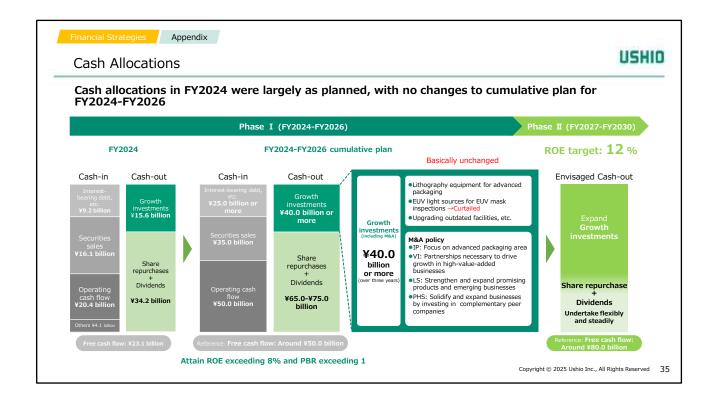








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USHIO Glossary A substrate that connects circuits on both sides with through-silicon vias and links multiple chips ΙP Industrial Processes Interposer ADP Advance Packaging Excimer An excimer lamp and units or devices equipped with it An approach to connecting multiple chips to facilitate communication between them A semiconductor manufacturing process that heats wafers to high temperatures Bridge Thermal process Projection lithography equipment that uses a step-and-repeat technique to expose patterns Dynamic digital connection: Improves positioning accuracy for die shift and rotation DDC Stepper Direct imaging: An exposure technique that draws patterns directly without using a mask Where chips placed on panel deviate from designed positions DI Die shift DI lithography equipment An advanced packaging field for 2xD and 3D integration of semiconductors, including chiplets Advanced packaging Uses direct imaging technique to draw patterns Digital Lithography Technology DLT Visual Imaging ٧I Refers to digital lithography systems. A direct imaging lithography equipment incorporating digital lithography technology developed through strategic partnership with Applied Materials LS Life Sciences DLT system Photonics Solutions PHS EUV Extreme Ultraviolet Radiation LCD Liquid Crystal Display ${\it Copyright @ 2025 \ Ushio \ Inc., \ All \ Rights \ Reserved} \qquad 36$

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